

# ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention	METHOD AND APPARATUS FOR AMPLITUDE FILTERING IN THE FREQUENCY PLANE OF A LITHOGRAPHIC PROJECTION SYSTEM
--------------------	---

Application Number : 10/604,519

Confirmation Number:

First Named Applicant: Shahid Butt

Attorney Docket Number: FIS920030150

Art Unit:

Examiner:

Search string: ( 5863712 ).pn

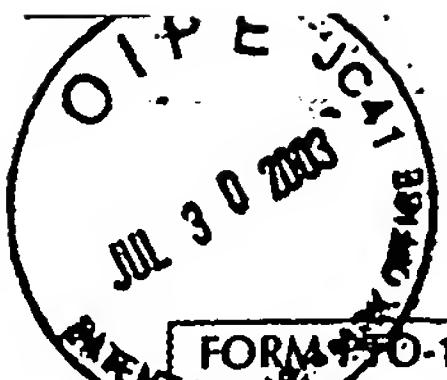
## US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	5863712	1999-01-26	Von Bunau et al.	+		

## Signature

Examiner Name	Date
<u>Alan Mathews</u>	<u>1-23-2005</u>



Sheet 1 of 1

FORM PTO-1449 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO.: FIS920030150US1	SERIAL NO.: 10/604,519
<u>SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT</u>		APPLICANT: Shabid Butt et al.	
(Use several sheets if necessary) (37 CFR 1.98(b))		FILING DATE: July 28, 2003	GROUP:

#### REFERENCE DESIGNATION

#### U.S. PATENT DOCUMENTS

EXAMINER INITIAL	PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUB-CLASS	FILING DATE IF APPROPRIATE
AA						
AB						
AC						
AD						
AE						
AF						
AG						
AH						
AI						
AJ						
AK						

#### FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY OR PATENT OFFICE	CLASS	SUB-CLASS	TRANSLATION YES	NO
AL							
AM							
AN							
AO							
AP							

#### OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

A.M	AQ	"Characterization of Super-Resolution Photolithography", H. Fukuda, R. Yamanaka, T. Terasawa, K. Hama, T. Tawa and S. Okazaki, IEEE, 4/1992, pages 3.2.1-3.2.4.
A.M	AR	"Resolution Enhancement by Oblique Illumination Optical Lithography Using a Pupil Filter", T. Horiuchi, Y. Takeuchi, S. Matsuo and K. Harada, IEEE, 1993, pages 27.3.1-27.3.4.
	AS	

EXAMINER Alan Mathews

DATE CONSIDERED

1-23-2005

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

ibmf100388000ids2